

Method and Device for Embossing of a Nanostructure

Abstract

This invention relates to a method for embossing of a nanostructure (13) from a nanostructure punch (5) into a punch surface (14) of a curable material (8) which has been applied to a substrate (7) with the following steps, especially following sequence:

- Alignment of the nanostructure (13) relative to the punch surface (14),
- Embossing of the punch surface (14) by
 - A) Prestressing of the nanostructure punch (5) by deformation of the nanostructure punch (5) and/or prestressing of the substrate (7) by deformation of the substrate (7),
 - B) Making contact of a partial area (15) of the punch surface (14) with the nanostructure punch (5) and
 - C) Automatic contacting of the remaining surface (16) at least partially, especially predominantly, by the prestressing of the nanostructure punch (5) and/or the prestressing of the substrate (7).

Figure 6c